

***IN THE UNITED STATES PATENT AND TRADEMARK OFFICE***

Applicant: Koichi WATANABE et al.

Title: SPUTTERING TARGET AND PROCESS FOR PRODUCING Si OXIDE FILM THEREWITH

Appl. No.: 10/573,406

International Filing Date: 9/22/2004
371(c) Date: 3/27/2006

Examiner: Jason Berman

Art Unit: 1795

Conf. No. 2973

PETITION FOR EXTENSION OF TIME

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Applicant hereby petitions the Commissioner under 37 C.F.R. §1.136(a) for a two-month extension of time for response in the above-identified application for the period required to make the attached response timely.

The extension fee for response within the second months is \$490.00.

A credit card payment form for this amount is enclosed herewith.

The Commissioner is hereby authorized to charge any additional fees which may be required regarding this application under 37 C.F.R. §§ 1.16-1.17, or credit any overpayment, to Deposit Account No. 19-0741. Should no proper payment be enclosed herewith, as by the credit card payment form being unsigned, providing incorrect information resulting in a rejected credit card transaction, or even entirely missing, the Commissioner is authorized to charge the unpaid amount to Deposit Account No. 19-0741.

Respectfully submitted,

Date November 22, 2010

By K. McHenry

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